The international journal & abstracting service for Vacuum Sciences & Technology

VACUUM

SURFACE ENGINEERING, SURFACE INSTRUMENTATION & VACUUM TECHNOLOGY

Volume 74, 2004

ELSEVIER

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Vacuum 74 (2004) III–XII

VACUUM
SURFACE ENGINEERING, SURFACE INSTRUMENTATION & VACUUM TECHNOLOGY

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doi:10.1016/S0042-207X(04)00210-6

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